Miika Mattinen

List of Publications by Year in Descending Order

35 papers	573 citations	16 h-index	23 g-index
36 ext. papers	711 ext. citations	5.6 avg, IF	4.03 L-index

#	Paper	IF	Citations
35	Atomic layer deposition of GdF3 thin films. *Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films*, **2022**, 40, 022402	2.9	0
34	Atomic layer deposition of TbF3 thin films. *Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films*, **2021**, 39, 022404	2.9	2
33	Atomic Layer Deposition of Insulating AlF3/Polyimide Nanolaminate Films. *Coatings*, **2021**, 11, 355	2.9	1
32	Highly conductive and stable CoS thin films by atomic layer deposition: from process development and film characterization to selective and epitaxial growth. *Dalton Transactions*, **2021**, 50, 13264-13275	4.3	
31	Atomic Layer Deposition of 2D Metal Dichalcogenides for Electronics, Catalysis, Energy Storage, and Beyond. *Advanced Materials Interfaces*, **2021**, 8, 2001677	4.6	12
30	Van der Waals epitaxy of continuous thin films of 2D materials using atomic layer deposition in low temperature and low vacuum conditions. *2D Materials*, **2020**, 7, 011003	5.9	13
29	Controlling Atomic Layer Deposition of 2D Semiconductor SnS2 by the Choice of Substrate. *Advanced Materials Interfaces*, **2020**, 7, 2001046	4.6	4
28	Atomic Layer Deposition of PbS Thin Films at Low Temperatures. *Chemistry of Materials*, **2020**, 32, 8216-8228	9.6	7
27	Studies on solid state reactions of atomic layer deposited thin films of lithium carbonate with hafnia and zirconia. *Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films*, **2019**, 37, 020929	2.9	5
26	Atomic Layer Deposition of Nickel Nitride Thin Films using NiCl2(TMPDA) and Tert-Butylhydrazine as Precursors. *Physica Status Solidi (A) Applications and Materials Science*, **2019**, 216, 1900058	1.6	4
25	Review Article: Atomic layer deposition of optoelectronic materials. *Journal of Vacuum Science and Technology B:Nanotechnology and Microelectronics*, **2019**, 37, 030801	1.3	34
24	Crystalline tungsten sulfide thin films by atomic layer deposition and mild annealing. *Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films*, **2019**, 37, 020921	2.9	10
23	Atomic Layer Deposition of Emerging 2D Semiconductors, HfS2 and ZrS2, for Optoelectronics. *Chemistry of Materials*, **2019**, 31, 5713-5724	9.6	36
22	Atomic Layer Deposition of Photoconductive CuO Thin Films. *ACS Omega*, **2019**, 4, 11205-11214	3.9	19
21	Nickel Germanide Thin Films by Atomic Layer Deposition. *Chemistry of Materials*, **2019**, 31, 5314-5319	9.6	5
20	Toward epitaxial ternary oxide multilayer device stacks by atomic layer deposition. *Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films*, **2019**, 37, 020602	2.9	3
19	Atomic Layer Deposition of PbI2 Thin Films. *Chemistry of Materials*, **2019**, 31, 1101-1109	9.6	34

18	Atomic Layer Deposition of Intermetallic Co3Sn2 and Ni3Sn2 Thin Films. *Advanced Materials Interfaces*, **2019**, 6, 1801291	4.6	8
17	Low-Temperature Wafer-Scale Deposition of Continuous 2D SnS Films. *Small*, **2018**, 14, e1800547	11	33
16	Atomic Layer Deposition of Rhenium Disulfide. *Advanced Materials*, **2018**, 30, e1703622	24	45
15	Atomic layer deposition of lanthanum oxide with heteroleptic cyclopentadienyl-amidinate lanthanum precursor - Effect of the oxygen source on the film growth and properties. *Thin Solid Films*, **2018**, 660, 199-206	2.2	7
14	Rhenium Metal and Rhenium Nitride Thin Films Grown by Atomic Layer Deposition. *Angewandte Chemie*, **2018**, 130, 14746-14750	3.6	2
13	Rhenium Metal and Rhenium Nitride Thin Films Grown by Atomic Layer Deposition. *Angewandte Chemie - International Edition*, **2018**, 57, 14538-14542	16.4	16
12	Diamine Adduct of Cobalt(II) Chloride as a Precursor for Atomic Layer Deposition of Stoichiometric Cobalt(II) Oxide and Reduction Thereof to Cobalt Metal Thin Films. *Chemistry of Materials*, **2018**, 30, 3499-3507	9.6	21
11	Atomic Layer Deposition of Molybdenum and Tungsten Oxide Thin Films Using Heteroleptic Imido-Amidinato Precursors: Process Development, Film Characterization, and Gas Sensing Properties. *Chemistry of Materials*, **2018**, 30, 8690-8701	9.6	16
10	Atomic layer deposition of crystalline molybdenum oxide thin films and phase control by post-deposition annealing. *Materials Today Chemistry*, **2018**, 9, 17-27	6.2	22
9	Atomic layer deposition of tin oxide thin films from bis[bis(trimethylsilyl)amino]tin(II) with ozone and water. *Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films*, **2017**, 35, 041506	2.9	12
8	Atomic Layer Deposition of Crystalline MoS2 Thin Films: New Molybdenum Precursor for Low-Temperature Film Growth. *Advanced Materials Interfaces*, **2017**, 4, 1700123	4.6	75
7	Atomic Layer Deposition of Zinc Glutarate Thin Films. *Advanced Materials Interfaces*, **2017**, 4, 1700512	4.6	2
6	Atomic Layer Deposition of Iridium Thin Films Using Sequential Oxygen and Hydrogen Pulses. *Journal of Physical Chemistry C*, **2016**, 120, 15235-15243	3.8	23
5	Low-temperature atomic layer deposition of copper(II) oxide thin films. *Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films*, **2016**, 34, 01A109	2.9	18
4	Scalable Route to the Fabrication of CHNHPbI Perovskite Thin Films by Electrodeposition and Vapor Conversion. *ACS Omega*, **2016**, 1, 1296-1306	3.9	32
3	Nucleation and Conformality of Iridium and Iridium Oxide Thin Films Grown by Atomic Layer Deposition. *Langmuir*, **2016**, 32, 10559-10569	4	24
2	Selective etching of focused gallium ion beam implanted regions from silicon as a nanofabrication method. *Nanotechnology*, **2015**, 26, 265304	3.4	5
1	Atomic layer deposition and characterization of Bi2Te3 thin films. *Journal of Physical Chemistry A*, **2015**, 119, 2298-306	2.8	23